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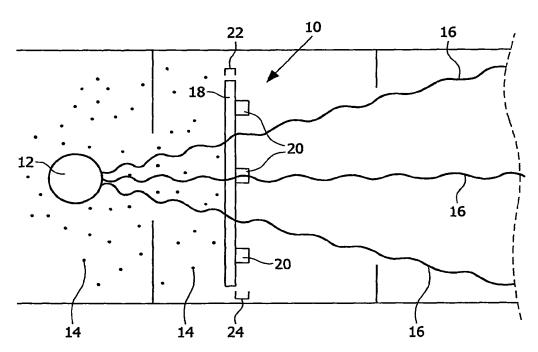
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(54) Title: FILTER FOR RETAINING A SUBSTANCE ORIGINATING FROM A RADIATION SOURCE AND METHOD FOR THE MANUFACTURE OF THE SAME



(57) Abstract: The invention describes a method of manufacturing a filter for retaining a substance originating from a radiation source, which filter comprises a thin layer that is transparent to extreme ultraviolet and/or soft X-ray radiation and which may be used inter alia in a device for EUV lithography. It is proposed that the filter (10) is high-temperature-resistant so as to render possible its use in particular for high-power radiation sources.

WO 2005/017624 A1



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